

Docket Number: 081468-0306399

Client Reference: P-0375.010-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re Application of:

KURT et al.

Confirmation No. 8782

Application No. 10/686,813

Group Art Unit: 1756

Filed: October 17, 2003

Examiner: UNKNOWN

Title: LITHOGRAPHIC PROJECTION APPARATUS  
AND DEVICE MANUFACTURING METHOD

\* \* \* \*

**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the reference listed on the attached PTO-1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

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Date: February 20, 2004

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Atty.  
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Client Ref.

306399

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# **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**

Applicant: KURT et al.

Appln. No.: 10/686,813

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Examiner:

Group Art Unit: 1756

## **U.S. PATENT DOCUMENTS**

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR						
	BR						
	CR						
	DR						
	ER						
	FR						
	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						

## **FOREIGN PATENT DOCUMENTS**

		Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
							Enclosed	No	Enclose	No
	NR									
	OR									
	PR									
	QR									
	RR									
	SR									
	TR									
	UR									
	VR									
	WR									

## **OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

	XR	SILVAST et al., "High-power plasma discharge source at 13.5 nm and 11.4 nm for EUV lithography," <i>Proc. SPIE</i> 3676:272-275 (1999)			
	YR				
	ZR				
	AAR				
	BBR				
	CCR				

Examiner

Date Considered:

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.